



S.S.N. 09/941,537

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Chen et al.

Group Art Unit: 1756

Serial No.: 09/941,537

Examiner: J. S. Ruggles

Filed: 08/29/2001

In Response to Office Action
Dated: 11/28/2003

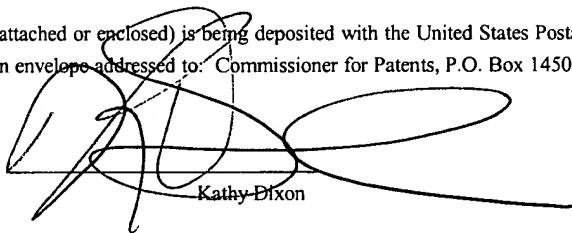
For: METHOD FOR REDUCING LIGHT REFLECTANCE IN A PHOTOLITHOGRAPHIC
DUAL DAMASCENE TRENCH PATTERNING PROCESS

Attorney Docket No.: 67,200-477

Certificate of Mailing

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, Va 22313-1450.

Date: December 11, 2003



Kathy Dixon

SUPPLEMENTAL AMENDMENT

Commissioner for Patents
Alexandria, Va 22313-1450

Dear Sir:

In response to an Advisory Action mailed 11/28/2003, Applicants respectfully request entry of the following amendments as previously suggested by Examiner in paper #4 since the Advisory Action does not indicate the amendments submitted as suggested by Examiner and submitted by Applicants have been entered. The Advisory Action indicates the Examiner has approved the drawing amendments in paper #3. Please consider the following remarks.